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[FR/FR]; Chemin des Franques, Parc Technologique des Fontaines, F-38926 Bernin (FR).

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(72) Inventors; and

(75) Inventors/Applicants (for US only): LETERTRE, Fabrice [FR/FR]; 40 chemin des Buclos, F-38240 Meylan (FR). FAURE, Bruce [FR/FR]; 10 rue du Vieux Temple, F-38000 Grenoble (FR). GUENARD, Pascal [FR/FR]; 3 Lotissement des Cerisiers, F-38190 Froges (FR).

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(74) Agent: BERTRAM, Rainer; Grünecker, Kinkeldey, Stockmair & Schwanhäusser, Leopoldstraße 4, 80802 München (DE).

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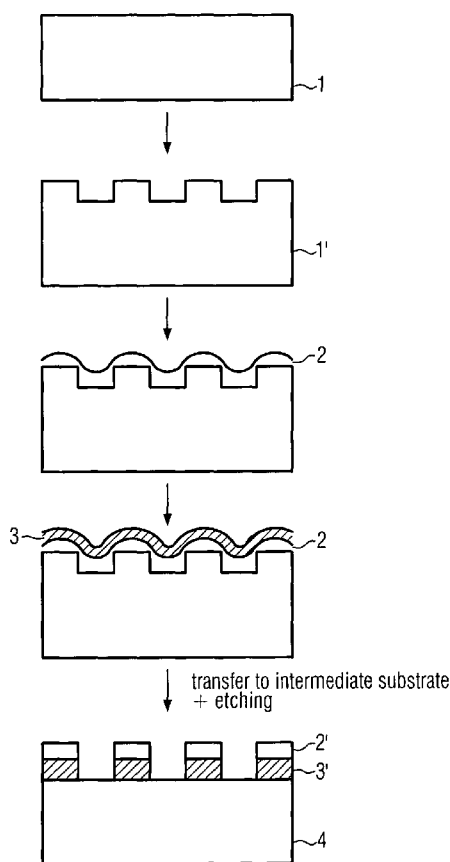
(71) Applicant (for all designated States except US): S.O.I. TEC SILICON ON INSULATOR TECHNOLOGIES

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(54) Title: RELAXATION AND TRANSFER OF STRAINED MATERIAL LAYERS

(57) Abstract: The present invention relates a method for the formation of an at least partially relaxed strained material layer, the method comprising the steps of providing a seed substrate; patterning the seed substrate; growing a strained material layer on the patterned seed substrate; transferring the strained material layer from the patterned seed substrate to an intermediate substrate; and at least partially relaxing the strained material layer by a heat treatment.

FIG. 1





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